Characterisation of the oxidation and creep behaviour of novel Mo-Si-Ti alloys

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Abstract

1 The oxidation and creep behaviour of novel eutectic-eutectoid Mo-Si-Ti alloys were studied and 2 compared to previously investigated entirely eutectic Mo-20Si-52.8Ti (at%) and eutectoid Mo-21Si-3 34Ti reference alloys [Schliephake et al. in Intermetallics 104 (2019) 133-142]. While the latter 4 reference alloys showed either outstanding oxidation behaviour in the temperature range of 800 to 5 1200 °C (eutectic alloy) or reasonable creep resistance (eutectoid alloy), a combination of both was 6 successfully achieved in a Ti-rich alloy variant (Mo-21Si-43.4Ti). The ubiquitous catastrophic oxidation 7 ("pesting") of Mo-based alloys at 800 °C is suppressed in this alloy and reasonable oxidation resistance 8 at higher temperatures is observed. For the first time, the unexpected oxidation resistance of the alloys 9 exhibiting eutectic volume fractions of more than 50 vol% is rationalised by a systematic deconvolution 10 of mass gain by scale formation and mass loss by evaporation of volatile species. Furthermore, creep is 11 revealed to be based on similar creep mechanisms throughout the alloy series. Therefore, the observed 12 improvement in creep resistance of the pesting-resistant Ti-rich alloy variant over the eutectic alloy is 13 attributed to the decreasing homologous temperature when testing both at 1200 °C.

1. Introduction

14 Many attempts have been made by international researchers with the purpose of optimising the Mo-Si 15 based alloy system in order to provide alternatives to Ni-based superalloys for high temperature applications. Most attention was paid to three-phase Mo-Si-B alloys which show very promising creep 16 17 performance and satisfactory oxidation behaviour in the temperature regime of 1000 to 1200 °C [1-3]. However, they all suffer from the pesting phenomenon at temperatures below 1000 °C [4] which 18 19 excludes them for wide industrial applications. Additionally, they possess significantly higher densities 20 in the range of 9.5 g/cm³ [5] compared to commercially used Ni-based superalloys. This drawback was 21 successfully alleviated by macro-alloying with Ti reducing the density to 7.7 g/cm³ [6, 7]. However, 22 inadequate oxidation resistance at intermediate temperatures below 1000 °C is still present in these 23 alloys [6]. The development of two-phase eutectic or eutectoid Mo-Si-Ti alloys in recent research work 24 by Schliephake et al. [8] shows great potential in this respect. The novel eutectic and eutectoid two-25 phase, fine-scaled Mo-Si-Ti alloys with comparably low density of 6 to 7 g/cm³ have shown to be either 26 oxidation-resistant in the entire temperature range or sufficiently creep-resistant. The binary eutectic 27 Mo-20Si-52.8Ti alloy consisting of Moss and (Ti,Mo)₅Si₃ lamellae possesses outstanding oxidation behaviour, namely insignificant and constant mass change subsequent to an initial parabolic oxidation
behaviour at 1100 and 1200 °C as well as absence of any pesting-like behaviour at 800 °C. This
unexpected oxidation resistance at 800 °C has been attributed to the formation of a mixed SiO₂-TiO₂
oxide scale [8]. In contrast, the eutectoid alloy Mo-21Si-34Ti comprising fine-structured Moss and
(Mo,Ti)₅Si₃ lamellae exhibits pesting behaviour at 800 °C, but reasonable creep resistance by means of
one order of magnitude lower minimum creep rate compared to the eutectic alloy.

In order to achieve both, oxidation and creep resistance, in a single alloy, we suggest to synthesise a eutectic-eutectoid microstructure in the present study. The former addition of B [9-12] is claimed to be redundant as it is believed that the fine-scaled eutectic and eutectoid microstructures enable fast surface diffusion paths and, thus, will lead to rapid passivation by oxide scale formation.

2. Experimental

38 The alloys presented in this paper were arc-melted using high-purity bulk elements Mo, Ti and Si with purities 99.95, 99.8 and 99.99 %, respectively, in an Edmund Bühler GmbH AM/0,5 Arc Melter 39 40 equipped with a water-cooled, button-shaped Cu crucible. Arc melting was conducted under Ar 41 atmosphere at 600 hPa which was cleaned from O residuals by pre-melting a Zr lump. Prior to melting, 42 the chamber was iteratively pumped and flooded with Ar before evacuating to 10^{-4} mbar. To guarantee 43 homogeneity, the melting procedure was repeated by turning over the button and re-melting it for at 44 least five times. The weight loss due to melting was confirmed to be below 0.5 wt%. The final shape of 45 the ingots was achieved by re-melting in a nugget-shaped Cu crucible. Additional heat treatments were 46 applied for specific alloys to complete the solid phase decomposition of (Mo,Ti)₃Si. These heat 47 treatments were conducted in a Gero tube furnace (HRTH sinter furnace) at 1300 °C for 200 h under Ar 48 atmosphere.

N and O impurities were determined by hot gas carrier extraction on a Leco TC500 device in order to determine. The N content was found to be below 0.004 at% and the O content in the order of 0.1 at% in all investigated alloys. The density was verified at room temperature by applying the Archimedes principle. The solidus temperature of the alloys and the Si content in Mo_{ss} were calculated by using the thermodynamic PANDAT software package (version of 2018) in conjunction with the commercially available database (PanMo2018a).

55 Oxidation and creep samples were manufactured by electrical discharge machining and prepared 56 according to the planned testing.

57 Cyclic oxidation experiments were conducted in static laboratory air at 800, 1100 and 1200 °C in muffle 58 furnaces provided by Gero and Nabertherm. The sample geometry was $(5 \times 5 \times 4) \text{ mm}^3$. Prior to 59 oxidation testing, the samples were ground to SiC grit P2500 to ensure appropriate surface finish. Mass 60 change was determined after each cycle at room temperature utilising a Sartorius balance at an accuracy 61 of 1 µg. The total test duration of the cyclic oxidation experiments was 100 h. The oxidation samples were maintained in ceramic Al₂O₃ baskets throughout the entire testing but were flipped after each cycle.
Isothermal oxidation experiments were carried out under synthetic air and Ar mixture with a ratio of 3:2
and flow rates of 30 ml/min and 20 ml/min, respectively, using a thermogravimetric analyser STA449
by Netzsch for continuous monitoring of the mass change. The oxidation samples were placed in Al₂O₃
baskets as well.

67 Compressive creep tests at constant true stress were performed under vacuum between 1050 and 68 1316 °C at true stresses ranging from 50 to 300 MPa. The universal testing machine was provided by 69 Zwick and was equipped with a vacuum furnace by Maytec. The load was applied to the compression 70 samples via punches which were made of SiC. The ground front faces of the samples were lubricated 71 by means of hexagonal BN.

72 Scanning electron microscopy (SEM) was conducted using backscatter electron contrast (BSE) in a LEO 73 EVO 50 SEM by Zeiss equipped with an energy dispersive X-ray spectroscopy (EDX) system. EDX 74 was used to characterise the obtained microstructures and oxide morphology of the oxidation samples. 75 Volume fractions were determined by manually denoting the various microstructural regions using the 76 image processing software Corel Photo-Paint and subsequent determination of areal fraction in the 77 software ImageJ. The equivalence of areal fraction and volume fraction was based on the assumed 78 isometry and isotropy of the investigated microstructures. Determination of the interface density P was 79 conducted by means of evaluation of binarised BSE images with the linear intercept method. The 80 morphology of the oxide scales was analysed by means of cluster analysis of binarised greyscale BSE 81 images. All 8-connected pixels were detected in the binary images, combined to regions of pixels, and 82 finally each region was colour-coded by utilising a self-made Matlab script.

83 X-ray diffraction (XRD) measurements were performed using a D2 phaser device of Bruker in Bragg-84 Brentano geometry operating with Cu K_{α} radiation. The Cu tube was operated at 30 kV and 10 mA, and 85 the according radiation was filtered by means of Ni foil. The radiation was detected using a LynxEye 86 line detector at a step size of 0.01 ° in 2 Θ with an accumulated time of 384 s per step. Lattice parameters 87 were determined by evaluating the corresponding peak positions with a Nelson-Riley approach [13].

3. Results and discussion

3.1. Alloy strategy and resulting microstructure

The alloy design strategy focuses on the development of novel Mo-Si-Ti alloys with tailored eutecticeutectoid microstructures comprising minor volume fractions of primary solidified Mo_{SS}. The starting points were the former investigated eutectic Mo-20Si-52.8Ti (green symbol in the relevant section of the liquidus projection of the ternary Mo-Si-Ti system, Fig. 1) and eutectoid Mo-21Si-34Ti (blue symbol) reference alloys in Ref. [8]. Two novel alloys within the chemical composition range framed by these two reference alloys were examined: (a) the Ti-rich alloy A Mo-21Si-43.4Ti (red symbol) being

- closer to the composition of the eutectic alloy and the Ti-lean alloy B Mo-21Si-38.7Ti (black symbol)
- 95 being near to the eutectoid alloy.



Fig. 1 Section of the liquidus projection of the ternary Mo-Si-Ti system highlighting the investigated alloys (coloured symbols) and the primary solidifying phases (grey labels).

Table 1 summarises the details of the chemical compositions of the investigated alloys and their microstructural characteristics. Note that alloy A does not require an additional heat-treatment since (Mo,Ti)₃Si decomposes completely during processing, as will be shown in the further course of this article, and is therefore characterised in the as-cast sate (designated ac in what follows). In contrast, alloy B contains (Mo,Ti)₃Si in the as-cast state, hence an additional heat-treatment (ht) at 1300 °C for 200 h under Ar atmosphere is applied to achieve complete eutectoid decomposition.

Table 1 Summary of chemical and microstructural data of the investigated alloys: nominal compositions x_i , volume fraction of primary solidified Moss $v^{Moss^{primary}}$, volume fractions of (Mo,Ti)₃Si $v^{(Mo,Ti)_3Si}$, eutectoid and eutectic regions $v^{eutectoid}$ and $v^{eutectic}$, phase boundary fraction *P* and density ρ . * in the heat-treated condition.

#	i	<i>x_i</i> / at%	v ^{Moss^{primary} / vol%}	v ^(Mo,Ti) 3 ^{Si} / vol%	v ^{eutectoid} / vol%	v ^{eutectic} / vol%	<i>P</i> / μm ⁻¹	ρ / g/cm ³
A	Мо	35.6	3.1 ± 1.2	-	46.7 ± 6.1	50.2 ± 6.3	0.6 ± 0.1	6.49
	Si	21						
	Ti	43.4						
В	Мо	40.3	6.8 ± 1.7	13.5 ± 4.0	36.7 ± 2.0	45.4 ± 3.5	$1.0 \pm 0.1*$	6.84
	Si	21						
	Ti	38.7						

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103 The corresponding microstructures of the investigated alloys including the eutectic and eutectoid 104 reference alloys are shown in the BSE micrographs in Fig. 2. The reference alloys comprise fully 105 lamellar eutectic and eutectoid microstructures, respectively, whereas the intermediate alloys are 106 characterised by a combination of both. The intermediate alloys are differently fine-scaled due to the 107 additionally applied heat-treatment of alloy B, as confirmed by the determination of the phase boundary density P (see Table 1). In the present study it is not possible to experimentally determine the chemical 108 109 composition of the silicide phase of the eutectic or eutectoid by EDX due to its fine-scaled 110 microstructure. Nonetheless, it is assumed that the eutectoid is composed of Moss and (Mo,Ti)₅Si₃ 111 lamella as z-contrast of the respective silicide lamella reveals a brighter grey level compared to the 112 silicide lamella of the eutectic. The contrast difference is mostly attributed to the different contents of 113 Mo (brighter) and Ti (darker) which occupy the respective lattice site(s) in either (Mo,Ti)₅Si₃ and $(Ti,Mo)_5Si_3$ while the Si remains virtually unaffected by the actual type of silicide. Nevertheless, 114 115 unambiguous evidence for the crystal structure of the respective 5-3 silicide cannot be provided by this 116 kind of images.



Fig. 2 BSE micrographs of the microstructures of the as-cast eutectic reference alloy (a), alloy A as-cast (b), alloy B heattreated at 1300 °C for 200 h (c) and the eutectoid reference alloy heat-treated at 1300 °C for 200 h (d). The seen phases/-regions are Mo_{SS} (bright), (Mo,Ti)₅Si₃ (light grey), (Ti,Mo)₅Si₃ (dark grey), lamellar eutectic (red highlighted) and lamellar eutectoid (blue highlighted) microstructures.

117 To further address the determination of the present phases, XRD analyses were performed in the as-cast

- 118 state of alloy A and the heat-treated condition of alloy B. The presence of Moss, and both, (Ti,Mo)₅Si₃
- and $(Mo,Ti)_5Si_3$ could be confirmed (see Suppl. 1).

120 In addition, the lattice parameters of Moss in the investigated alloys were determined and compared to 121 the lattice parameters of binary bcc Mo-Ti solid solutions reported in literature [14] as shown in Fig. 3. This comparison allows for a determination of the phase specific Ti content in the bcc solid solution 122 123 when the Si contribution to the lattice parameter is neglected and considered to be similar among the 124 alloy series. These considerations are assumed to be appropriate as Sturm et al. have shown that the lattice parameter of Mo-Si solid solutions only decreased by 0.2 % when 3.34 at% Si were added [15]. 125 126 Furthermore, thermodynamic calculations predict a maximum Si content in Moss of 4 at% in all 127 investigated alloys when the solidification process starts. By taking the applied manufacturing route of 128 arc melting with subsequent heat treatment in some cases into account, it is likely that present Moss 129 comprises Si in the order of 2 to 4 at% (4 at% in case of arc-melted, fast-cooled specimen and lower for 130 heat-treated, slowly-cooled samples). The phase specific composition – especially the one of the bcc 131 solid solution – is a crucial parameter for the assessment of oxidation behaviour in the further course of 132 this article but is typically difficult to be reliably determined due to the rather fine scale morphology of 133 the phases. Furthermore, local TEM investigations of the Ti content in the Moss lamellae in the eutectic 134 or eutectoid might certainly be more accurate but due to the small investigated volume, fluctuations 135 among different regions, namely primarily solidified Moss, lamellae adjacent to and (Mo,Ti)₅Si₃ vs. 136 lamellae adjacent to (Ti,Mo)₅Si₃, remain difficult to be addressed. Therefore, the here presented 137 evaluation only holds true for the average Ti content in Moss including the overall microstructure, especially in the intermediate eutectic-eutectoid alloys A and B, including both, eutectic and eutectoid 138 139 regions, which possibly possess different Ti contents on local scale. These differences have to be 140 assessed in future work. The lattice parameters of Moss in the reference alloys frame the intermediate 141 eutectic-eutectoid alloys well. In general, a consistently lower Ti content in Moss in contrast to the 142 nominal Ti content could be determined in all investigated alloys. This reveals that Ti is significantly 143 solved in the silicide phases. The eutectic alloy possesses the largest Ti-concentration in Moss at 45 at%, 144 while the eutectoid allow represents the lower limit with only 17 at% Ti. The intermediate allows 145 comprise average, global Ti contents of around 35 at% (alloy A) and 25 at% (alloy B). However, an estimated inaccuracy of the lattice parameters of maximum 0.001 Å leads to an uncertainty in the 146 147 determination of the Ti content of approximately 1.4 at% in the eutectic alloy and more than 5 at% in 148 the eutectoid alloy.



Fig. 3 Experimentally determined lattice parameters of Moss in the investigated alloys compared to the lattice parameters of binary Mo-Ti solid solution as a function of Ti content reported in Ref. [14] and compared to the eutectic and eutectoid reference alloys evaluated in Ref. [8]. The semi-transparent regions indicate the estimated uncertainty of the lattice parameters and its conversion to the Ti content. Arrows at the abscissa indicate the nominal Ti contents of the alloys.

3.2. Oxidation behaviour

149 All aforementioned alloys including the eutectic and eutectoid reference alloys were subjected to isothermal and cyclic oxidation tests at 800, 1100 and 1200 °C. The specific weight changes, at least 150 151 three samples in each case, in dependence of test duration during cyclic oxidation tests at 800 and 152 1200 °C are plotted in Fig. 4. The results gained at 1100 °C are included in supplementary material to this article (Suppl. 2) as similar oxidation behaviour to 1200 °C is observed. As 800 °C is the critical 153 154 temperature where pesting occurs, the corresponding isothermal oxidation tests of alloy A and B are 155 included as well. The following results can be concluded from these experiments: (i) The previously reported results on the oxidation behaviour of the eutectic and eutectoid reference alloys by Schliephake 156 157 et al. [8] are very well reproduced (see Suppl. 3). The eutectic alloy exhibits low mass changes in the 158 entire temperature range. In contrast, the eutectoid alloy shows catastrophic oxidation at 800 °C, and 159 slightly larger mass changes compared to the eutectic alloy at higher temperatures with significant 160 scatter between different samples. Nevertheless, the mass changes saturate after some duration of 161 exposure. (ii) Both alloys with intermediate Ti contents (A and B) exhibit different oxidation behaviour 162 but with significant similarities to the reference alloys. While alloy B suffers from pesting at 800 °C like 163 the eutectoid alloy and conventional Mo-Si based alloys [6, 16], alloy A shows similar adequate oxidation resistance like the eutectic alloy at 800 °C, but with slightly larger weight change after 100 h 164 by means of (-2.0 ± 0.7) g/cm² compared to (0.1 ± 0.1) g/cm² in the eutectic alloy. At 1200 °C, all alloys 165 show comparable adequate oxidation behaviour with reasonable mass changes in the range of 166

167 $(3.1 \pm 0.1) \text{ g/cm}^2$ (eutectic), $(-14.8 \pm 12.3) \text{ g/cm}^2$ (eutectoid), $(2.7 \pm 1.9) \text{ g/cm}^2$ (A), and $(-13.2 \pm 15.9) \text{ g/cm}^2$ (B). However, some scatter in mass change is present at higher temperatures, which is 169 attributed to local inhomogeneity of the as-cast and heat-treated microstructure, respectively.



Fig. 4 Specific weight change as a function of time during cyclic and isothermal oxidation for the investigated alloys A and B at 800 °C (a), and for cyclic oxidation at 1200 °C (b).

170 Additionally, isothermal oxidation tests at 800 °C were performed revealing similar trends in isothermal mass change for all investigated alloys (see Suppl. 4 for isotherms at 1100 and 1200 °C of all 171 investigated alloys). It was shown that (i) at 800 °C no pesting occurs, even not in alloy B which is 172 173 contrary to the cyclic oxidation experiments and most probably due to the absence of thermally induced 174 loading provoking oxide scale cracking and the Ar to synthetic air ratio. (ii) Slightly higher mass gain 175 in alloy A and B in the order of 5 g/cm² (1100 °C) and 20 mg/cm² (1200 °C) at temperatures above 176 800 °C which is most likely to be caused by the flowing synthetic air leading to higher O activity at the 177 surface.

SEM analyses of cross sections subsequent to cyclic oxidation after exposure times of 1 h and 100 h 178 179 were performed in order to investigate the oxide scale morphology. Representative BSE micrographs of oxidised samples of alloy A at 800 °C are depicted in Fig. 5. The initial oxidation during the first hour 180 of exposure at 800 °C is characterised by the formation of an outer TiO₂-rich oxide scale with locally 181 182 minor adherence, as cracking at the oxide scale substrate interface is observed (see Fig. 5a) and internal oxidation which occurs preferentially in the eutectoid regions close to the surface (see Fig. 5a and b). 183 184 This confirms the strikingly different oxidation behaviour of the eutectic and eutectoid at 800 °C. The 185 former Moss lamellae or primary solidified Moss either oxidise internally to (Ti,Si)-oxide guiding the oxidation attack towards the internal of the substrate, or if located at the surface oxidise to TiO₂ which 186 187 covers the surface while enabling O inward diffusion. This is remarkable as primary solidified Moss 188 might directly oxidise to MoO₃ leaving pores behind upon exposure to air. In this study, it is assumed 189 that formed MoO_3 is evaporating quickly in alloy A, as some pores are enclosed in the internal oxidation 190 zone (see Fig. 5a). Nevertheless, the mass loss is probably compensated by the simultaneous rapid 191 formation of TiO_2 which is enabled by the rapid outward diffusion of Ti. Therefore, the suppression of 192 pesting in alloy A is attributed to the high average Ti content of Moss lamellae within the eutectic and

- 193 eutectoid regions being approximately 35 at%. However, due to the different oxidation behaviour of the
- 194 eutectic and eutectoid regions, it is likely that the oxidation-resistant eutectic region comprises a higher
- $195 \qquad \text{local Ti content in } Mo_{\text{SS}}. \text{ The oxidation-resistant eutectic alloy reveals a Ti content in } Mo_{\text{SS}} \text{ of } 45 \text{ at}\%.$
- 196 In contrast to both, the eutectoid alloy suffering from pesting contains only 17 at% Ti in Moss. After
- 197 100 h, the outer TiO₂ oxide scale measures an average thickness of $(4 \pm 2) \mu m$, with an internal oxidation
- 198 zone measuring $(23 \pm 10) \mu m$ in thickness in alloy A.
- 199 Additionally, pre-oxidation experiments of alloy A at 1100 °C for 10 h in laboratory air lead to the 200 formation of a mixed SiO₂-TiO₂ oxide scale with an average thickness of less than 10 μ m. It enables the 201 substrate to withstand cyclic oxidation experiments at 800 °C for 100 h without significant internal 202 oxidation, as was observed for non-pre-oxidised samples. Furthermore, the adequate specific weight 203 change is in the range of less than 3 mg/cm^2 (see Fig. 5c). This might be due to the dense oxide scales 204 formed at 1100 °C after 10 h hindering further inward O diffusion at 800 °C and therefore preventing 205 internal oxidation. Furthermore, the oxide scale (originally formed at 1100 °C after 10 h) growth at 206 800 °C is retarded compared to the observations made for the cyclic oxidised samples at 1100 °C for 207 100 h. Under isothermal conditions at 800 °C alloy A reveals a thin SiO₂-TiO₂ mixed oxide scale with 208 a thickness of less than 5 µm in average without any indications of internal oxidation as shown in Fig. 209 5d. The thin and continuous oxides scale might be attributed to the absence of thermo-cycling induced 210 cracking and is in well agreement with the negligible mass change detected.



Fig. 5 Representative BSE micrographs of the cyclic oxidised samples at 800 °C after 1 h (a) and 100 h (b) of alloy A; preoxidised sample (1100 °C/10 h/air) of alloy A after cyclic oxidation at 800 °C for 100 h (c) and after isothermal oxidation at 800 °C for 100 h (d).

In comparison to the oxidation behaviour of the investigated alloy A, the eutectic reference alloy exhibits a very thin, continuous mixed SiO₂-TiO₂ oxide scale after 1 h exposure time at 800 °C which grows to a thickness of only $(5 \pm 1) \mu m$ in average after 100 h without any internal oxidation (see Suppl. 5a and b). These results confirm the reproducibility of the oxidation behaviour of the eutectic alloy previously presented in Ref. [8].

216 In contrast, the Ti-lean alloy B suffers from pesting under cyclic testing conditions. Due to the significant 217 oxidation attack, cracking in the oxide scale and the internally oxidised substrate even after 1 h, a 218 difference between the eutectic and eutectoid regions in oxidation behaviour could not be observed, as 219 shown in Fig. 6a. Although pesting is observed like in the eutectoid reference alloy, it is less severe, as 220 mass losses stabilise after approximately 20 h and only partial material disintegration with local spalling 221 is observed (see Suppl. 5c and d). It seems that alloy B might not be oxidation-resistant itself or that the 222 eutectic regions were not able to protect it from pesting. The main reasons might be: (i) The Ti content 223 in Moss is only about 25 at%, being remarkably lower than that of the eutectic alloy and alloy A, which 224 might be insufficient to enable TiO_2 formation and to reduce the probability of MoO_3 formation. Thus, 225 it is assumed that there exists a Ti-threshold content for Moss which determines whether pesting occurs, 226 or not. (ii) The volume fraction of the eutectic microstructure is in the range of (50 ± 6) vol% in alloy A 227 in contrast to (45 ± 3) vol% in alloy B. The volume fraction and distribution of the eutectic is likely to play a decisive role when suppressing pesting as in alloy A an almost binary eutectic network is present 228 229 which enables quick coverage of the surface accompanied with bridging eutectoid regions. Thereby, in 230 alloy A locally present primary solidified Moss does not disturb oxide scale formation at the surface but 231 oxidises internally itself. It is assumed that due to the low Ti content in Moss and the higher volume 232 fraction of eutectoid microstructure in alloy B, MoO₃ formation was dominant leading to pesting. The 233 aforementioned striking difference in oxidation behaviour at 800 °C between cycylic and isothermal 234 oxidation testing is supported by Fig. 6b and c. It is revealed that a thin, continuous and especially 235 crack-free mixed SiO₂-TiO₂ oxide scale forms under isothermal conditions preventing catastrophic 236 oxidation.



Fig. 6 Representative BSE micrographs of alloy B after 1 h cyclic (a) and isothermal oxidation (b) at 800 °C and after 100 h isothermal oxidation at 800 °C.

- At 1100 and 1200 °C, an outer TiO₂ oxide scale is formed with an underlying SiO₂-TiO₂ duplex scale
- 238 on all investigated intermediate alloys. Fig. 7 shows oxidised samples at 1200 °C; due to the similarity
- of the oxide scale morphology, the cross sections at 1100 °C are omitted. This was also observed on the
- 240 eutectic and eutectoid reference alloys (see Suppl. 5e and f).



Fig. 7 Representative BSE micrographs of the cyclic oxidised samples at 1200 °C after 100 h of alloy A as-cast (a) and alloy B heat-treated (b).

The corresponding oxide scale evolution at $1200 \,^{\circ}\text{C}$ is addressed by the oxide scale thickness and the respective SiO₂ volume fraction in the SiO₂-TiO₂ duplex scale after 100 h in Fig. 8. A trend seems to be present regarding the evolution of the absolute oxide scale thickness in dependence of the nominal Ti

content in the investigated alloys (see Fig. 8a). While the eutectic alloy possesses the thinnest oxide

245 scale with an absolute thickness of 50 µm in average (52.8 at% nominal Ti), the eutectoid alloy exhibits 246 the thickest oxide scale with about 80 µm in thickness (34 at% nominal Ti). The intermediate alloys A 247 and B range in between, namely 70 μ m and 75 μ m, respectively, pronouncing a trend towards increase in oxide scale thickness with decreasing nominal Ti content. This is somehow mirrored in the depth of 248 249 the internal oxidation as well, which is increasing with decreasing nominal Ti content, namely from 250 $10 \,\mu\text{m}$ in the eutectic alloy to approximately 55 μm in the eutectoid alloy. This trend might be supported 251 by the eutectic volume fraction in the investigated alloys, which is continuously decreasing from almost 252 100 vol% in the eutectic alloy, to 50 vol% in alloy A to 45 vol% in alloy B and zero in the eutectoid 253 alloy. These conclusions might be further correlated to the suppression of pesting at 800 °C, which is 254 achieved in the Ti-rich alloy A and the eutectic reference alloy. When considering the volume fraction 255 of SiO₂ in the SiO₂-TiO₂ duplex scale as depicted in Fig. 8 as well, it can be revealed that the SiO₂ 256 volume fraction is in the same range for all investigated alloys, meaning 52 vol% (eutectic alloy), 257 48 vol% (alloy A), 43 vol% (alloy B) and 47 vol% (eutectoid alloy).



Fig. 8 Volume fraction of SiO₂ in the SiO₂-TiO₂ duplex scale on cyclic oxidation samples after 100 h at 1200 °C and the corresponding oxide scale thicknesses of the investigated alloys A, B and the reference alloys.

258 However, conclusions on the matrix forming oxide drawn from the results on the volume fraction of the 259 respective oxides in the SiO₂-TiO₂ duplex scale have to be regarded with precautions. The determination 260 of the matrix forming oxide is not trivial as the growth kinetics of the individual oxides, their interactions 261 and mass loss due to evaporation play a crucial role. Therefore, the matrix forming oxide cannot be 262 solely identified based on the volume fraction of the respective oxides. Especially, the evaluation of 2D 263 micrographs does not provide any information on the 3D network structures of the SiO₂ and TiO₂ oxides, which is decisive for the determination of the matrix forming oxide. The representative BSE 264 265 micrographs of the oxide scales formed on alloy A and alloy B at 1200 °C after 100 h shown in Fig. 7

might lead to the suggestion that SiO₂ could be the matrix forming oxide in the SiO₂-TiO₂ duplex scale 266 267 as many SiO_2 regions seem to be connected. These apparent connections can be further assessed by pixel connectivity analysis as depicted in Fig. 9 for the eutectic reference alloy, the intermediate alloys A and 268 269 B and the eutectoid reference alloy. Pixel clusters of TiO₂ correspond to cold colours (blue to green) and 270 SiO_2 clusters to warm colours (red to yellow). In the eutectic reference alloy, several SiO_2 clusters are homogenously distributed within the duplex scale, however these are only laterally connected within 271 272 regions of approximately 20 to 60 µm (see Fig. 9a). In contrast, the segmentation of TiO₂ reveals a 273 penetrating network structure leading to the assumption that TiO_2 might be the matrix forming oxide. 274 The same SiO_2 network structure within the duplex scale is observed in alloy A, where several SiO_2 275 clusters are present, though they do not penetrate the oxide scale in its full depth, as shown in Fig. 9b. 276 Penetrating TiO_2 pathways are present, as well. This appearance is also observed in alloy B where the 277 SiO_2 regions are mostly isolated horizontally, as depicted in Fig. 9c; whereas TiO_2 is revealed to form a 278 continuous 2D network within large areal fractions of the SiO₂-TiO₂ duplex scale. Taking the eutectoid 279 reference alloy into account (see Fig. 9d), it is revealed that all alloys, both reference alloys and the 280 intermediate eutectic-eutectoid alloys mostly reveal a fine-structured, but discontinuous 2D SiO₂ 281 network within the SiO₂-TiO₂ duplex scale including penetrating pathways of TiO₂ connecting the oxide 282 surface with the substrate. Therefore, the significance of SiO₂ (as matrix forming oxide or high volume 283 fraction) in the oxide scale, as highlighted in previous research on Ti₅Si_{3±x} at 1000 °C [17], (Mo,Ti)₅Si₃ between 750 °C and 1300 °C [18, 19] and Mo-Si-B-Ti-Fe alloys at 1100 °C [20], might be less relevant 284 in order to achieve reasonable oxidation resistance, since both intermediate alloys are reasonably 285 286 oxidation-resistant at 1200 $^{\circ}$ C like both reference alloys even with locally penetrating TiO₂ pathways.



Fig. 9 Colour-coded images of the oxide scales formed on the eutectic reference alloy (a), alloy A (b), alloy B (c) and the eutectoid reference alloy (d) at 1200 °C after 100 h. SiO₂ is coloured in warm colours (red to yellow) and TiO₂ in cold (blue to green). Penetrating pathways in TiO₂ are highlighted as black, arrowed line.

287 Several conclusions can be drawn from the oxide scale thickness, the corresponding volume fraction of SiO₂ in the SiO₂-TiO₂ duplex scale as addressed in Fig. 8 and the oxide cluster analysis depicted in Fig. 288 289 9: (i) The probably expected correlation of less nominal Ti content in the alloy substrate leading to an 290 increased volume fraction of SiO_2 in the SiO_2 -TiO₂ duplex scale could not be observed. (ii) The absolute 291 oxide scale thickness shows a continuously increasing trend with decreasing nominal Ti content. (iii) The SiO₂-TiO₂ duplex scale does not necessarily has to comprise an SiO₂ matrix in order to enable 292 293 reasonable oxidation resistance at 1200 °C. This was proven by the presence of TiO₂ pathways 294 penetrating the oxide scale from its surface to the interface with the alloy substrate. This trend might be 295 extrapolated as a general result to 1100 and 800 °C, respectively. The penetrating pathways are 296 especially observed in the intermediate alloys A and B, whereas the eutectoid alloy most likely possesses 297 an SiO₂ matrix. Moreover, the eutectoid alloy reveals a rather high volume fraction of SiO₂, but the most 298 severe internal oxidation. In contrast, the eutectic alloy comprises an internal corrosion zone of only 299 10 μ m in depth with a comparable amount of SiO₂ in the SiO₂-TiO₂ duplex scale. These assumptions 300 might hold true for the lower test temperatures as well. This is in contrast to the conclusions drawn in 301 literature where SiO₂ is assumed to be the matrix forming oxide in order to achieve suitable oxidation 302 resistance [17-20]. (iv) All alloys are comparably fine-structured as confirmed by the determination of 303 the interface density. It can be concluded that the oxide scale formation, growth and morphology are 304 dependent on the nominal chemical composition and are a function of the test temperature.

Unambiguously, 800 °C is the critical temperature and therefore, of main interest to develop a further 305 306 understanding of the oxidation mechanisms in the investigated alloys. However, as the alloys show 307 either excellent oxidation resistance, being accompanied with very thin oxide scales (eutectic reference 308 alloy and alloy A), or pesting behaviour (eutectoid reference alloy and alloy B), a systematic assessment 309 of differences and similarities among the entire alloy series is not possible for this temperature. 310 Therefore, the following analysis strategy is applied to the results obtained at 1200 °C and for 100 h of 311 cyclic oxidation. Although, 1200 °C are selected, it is assumed that the results can be transferred to 312 lower temperatures. This assumption is mainly based on the different nature of the present oxidation 313 processes.

It is still questionable whether the forming oxide scales are passivating or if the evaporation of MoO₃ is dominating, as the experimentally determined weight change m^{exp} represents the balance of mass gain m_O^{scale} due to oxide scale growth by incorporation of O and mass loss m_{MO}^{vapour} due to evaporation of Mo in form of MoO₃:

$$\frac{m^{exp}}{A} = \frac{m_0^{scale}}{A} + \frac{m_{M_0}^{vapour}}{A}$$
(1)
with $\frac{m_0^{scale}}{A} \ge 0$ and $\frac{m_{M_0}^{vapour}}{A} \le 0$.

318 Nevertheless, the detailed mock-up of the formed scales is known by the previously shown 319 microstructural investigations in Fig. 8: the thicknesses of the sublayers (d^{top} for the top TiO₂ layer,

 d^{duplex} for the duplex layer) and volume fractions of the formed oxides are known ($v_{SiO_2}^{duplex}$ and 320 $v_{TiO_2}^{duplex}$). This permits to calculate m_0^{scale} and deduce $m_{M_0}^{vapour}$ from Eq. (1). Therefore, several 321 322 assumptions are made: (i) the internal oxidation is at first neglected (However, it is not considered to be 323 negligible as its impact is increasing in the alloys with decreasing nominal Ti content. Therefore, the 324 changes by considering internal oxidation are qualitatively assessed at the end of the Section), (ii) the 325 TiO_2 top layer is growing outward and (iii) the SiO_2 -TiO₂ duplex scale inward (as has been proven in a 326 three-phase Mo-Si-B-Ti alloy system by Azim et al. in Ref. [6]). The resulting mass loss at 1200 °C after 100 h due to evaporation m_{Mo}^{vapour} is in the order of (-7 ± 2) mg/cm² (eutectic), (-10 ± 2) mg/cm² 327 328 (alloy A), (-16 ± 5) mg/cm² (alloy B) and (-27 ± 4) mg/cm² (eutectoid). Please note that experimental 329 mass change and microstructural data (thicknesses and volume fractions) of one and the same sample 330 were used in the calculation for each mass loss. The error bars represent a conservative estimate of the limits of the method by considering the standard deviations of the measured oxide scale thicknesses. 331 332 Details of the calculation are provided in the Appendix. The varying impacts of the molar masses need 333 to be considered, as the evaporating Mo possesses a significantly higher molar mass compared to incorporated O. Therefore, the respective amounts of n_{Mo}^{vapour} , n_{Si}^{scale} and n_{Ti}^{scale} are calculated. The 334 according formulas for these quantities are also appended to this article (see Appendix). 335

336 The results are summarised in Fig. 10. The upper bar chart displays the evolution of the amount of 337 reacting, metallic species for the entire alloy series. It is revealed that the amount of Si being oxidised is almost constant, while the amount of Ti is slightly increasing. In contrast, the amount of Mo being 338 339 evaporated is significantly increasing. When taking the ratio of the oxidised Si and Ti atoms and the 340 evaporated Mo atoms into account (lower bar chart), it can be concluded that the extent of solid oxide 341 scale growth of the investigated alloys is comparable, but the evaporation is gaining dominance with 342 decreasing nominal Ti content. Moreover, the corresponding ratios of the nominal chemical composition 343 in the alloys are within 2.7 (eutectic) and 1.2 (eutectoid). These ratios correlate well with the observed 344 trend but are significantly lower than the ratio observed for the oxidation processes. Ti and Si are 345 significantly more consumed during oxidation as provided by the substrate in the eutectic alloy and alloy A. This difference is much smaller for alloy B and the eutectoid alloy. It is suggested that the 346 347 MoO_3 evaporation is more pronounced in Mo-rich alloys, especially in alloy B and the eutectoid alloy, due to probable less passivating character of the formed oxide scales. Moreover, the calculation 348 349 resembles a conservative approach. If the internal oxidation would have been considered, then the absolute value of m_{Mo}^{vapour} would be reduced, as the amount of oxygen uptake would be increased while 350 351 the experimental mass change would be the same (see Eq. (1)), and the drawn conclusions might be 352 even more shifted towards an intense scale formation. When taking the variations of the experimentally 353 determined mass changes with time of both reference alloys into account, it is obvious that different 354 characteristics are exhibited. In the eutectic reference alloy, the mass changes stabilise after 50 h and it 355 seems that the oxide scale growth is dominant. In contrast, in the eutectoid reference alloy the mass

changes are still declining after 100 h highlighting the significance of ongoing evaporation.
Conclusively, the oxide scales forming on the eutectic alloy are regarded as passivating, whereas on the
eutectoid alloy they do not seem to be entirely dense and, therefore, enabling further evaporation.



Fig. 10 Calculated amounts of oxidised Ti and Si; and Mo being evaporated at 1200 °C after 100 h in the investigated alloys and the corresponding ratio of the solid oxidised species Ti and Si; and evaporated Mo.

3.3. Creep behaviour

As alloy A shows satisfactory oxidation resistance between 800 and 1200 °C, it was subjected to 359 360 compressive creep testing in order to verify that a successful combination of oxidation and creep 361 resistance was achieved. Fig. 11a shows the true compressive creep rate as a function of true strain at 362 1200 °C and at stresses ranging from 50 to 300 MPa. The evolution of strain rate in dependence of true 363 strain is characterised by minimum creep rates, which are highlighted by square markers. This applies 364 to both reference alloys, the eutectic and the eutectoid as well; as previously shown in Ref. [8]. The 365 minimum creep rates are attained in alloy A after 1 - 2.5 % true strain after a significant drop in creep 366 rate during the primary creep stage has been observed. While the true strain attained at the creep rate 367 minimum is increasing with decreasing true stress in the range of 100 - 300 MPa, there seems to be a change in creep mechanism at 50 MPa as a slight decrease in true strain is observed compared to 368 369 100 MPa. A change in creep mechanism is further indicated by the less pronounced transient creep rate 370 drop at 50 MPa. Diffusional creep seems to become more relevant due to sufficient duration of loading.

Minimum true creep rates in dependence of the true compressive stress are summarised in the doublelogarithmic Norton plot shown in Fig. 11b and compared to the eutectic and eutectoid reference alloys and the corresponding monolithic phases. Alloy A exhibits an intermediate creep resistance in comparison to the eutectic and eutectoid alloys. By comparing the creep resistance of the monolithic

375 phases Ti₅Si₃, Mo₅Si₃ and single-phase (Mo,Si,B)_{SS}, it is obvious that these frame the creep behaviour

of all investigated alloys. Thereby, the creep resistance of the eutectic and eutectoid reference alloys is dominated by the less creep resistant phase $(Ti,Mo)_5Si_3$ and the improved creep resistant phase $(Mo,Ti)_5Si_3$, respectively.

379 The stress exponent *n* of the power law for $\dot{\varepsilon}_{min}$:

$$\dot{\varepsilon}_{min} \propto \sigma^n$$
 (2)

380 was determined to be 3.5 in alloy A, revealing similar creep characteristics as the eutectic and eutectoid

reference alloys which exhibit stress exponents of 3.7 and 3.5, respectively [8]. This indicates that creep

is dislocation climb controlled throughout the alloy series as was also found by Schliephake et al. in the

 $383 \qquad former \ developed \ three \ phase \ Mo-Si-B-Ti \ alloys \ (Mo_{SS} + (Ti,Mo)_5Si_3 + Mo_5SiB_2) \ [7].$

384 The apparent activation energy of creep Q_c in alloy A based on the Arrhenius term for $\dot{\varepsilon}_{min}$:

$$\dot{\varepsilon}_{min} \propto e^{-\frac{Q_c}{RT}}$$
 (3)

385 was determined at a true stress of 200 MPa and was found to be 484 kJ/mol (see Suppl. 6). In 386 comparison, the activation energies in the eutectic and eutectoid reference alloys were determined to be 387 471 kJ/mol and 444 kJ/mol supporting above statement of similar creep characteristics [8]. As the 388 apparent activation energies of both reference alloys and alloy A are in the same order and similar/same 389 creep mechanism are active in all alloys, the minimum true creep rate at a specific, absolute temperature 390 can be normalised to the solidus temperature and plotted in an Arrhenius plot as shown in Fig. 11c. This 391 plot utilising inverse homologous temperatures finally leads to a single master straight for all 392 investigated alloys. This proves that the observed difference in creep resistance at 1200 °C is caused by 393 the different applied homologous temperatures. Conclusively, the argumentation of the increased creep 394 resistance of the eutectoid alloy and of the eutectoid region in the intermediate alloys in general, cannot be based solely on the presence of $(Mo,Ti)_5Si_3$. This is further confirmed by an additional compression 395 396 creep test of alloy A at an increased temperature of 1318 °C which is equivalent to the homologous 397 temperature of 0.74 at which the eutectic reference alloy has been compression creep tested. This 398 compression creep test was conducted at 100 MPa and is highlighted with a bright red diamond marker 399 in Fig. 11b. Both, the intermediate alloy A and the eutectic reference alloy exhibit comparable creep 400 resistance when the tests were performed at identical homologous temperature.



Fig. 11 Compressive true stress curves of alloy A (a), the corresponding Norton plot with literature data for comparison [3, 8, 21, 22] (b) and Arrhenius plot utilising inverse homologous temperature for alloy A and the reference alloys (c).

4. Summary and Conclusion

401 Novel, fine-structured Mo-Si-Ti alloys with tailored eutectic-eutectoid microstructure were successfully 402 developed in this paper, namely a Ti-rich alloy A and a Ti-lean alloy B. Amongst all alloys, including 403 the eutectic and eutectoid reference alloys, it was found that, in addition to the eutectic reference alloy 404 [8], pesting could be suppressed at 800 °C in the novel alloy A. This was attributed to a threshold in 405 nominal Ti content of minimum 43 at% and average Ti content in Moss lamellae in eutectic and eutectoid regions of minimum 35 at%, respectively, combined with at least 50 vol% eutectic regions 406 which presumably balance the pesting nature of the eutectoid. At higher temperatures of 1100 and 407 408 1200 °C all investigated alloys revealed a top TiO₂ layer with an underlying TiO₂-SiO₂ duplex scale 409 providing suitable oxidation resistance. The duplex scale seems to be essential to guarantee adequate 410 oxidation resistance, as sole TiO_2 is believed to be non-protective due to its high diffusion coefficient 411 for O [23] and its proneness to cracking [24]. Most recent thermodynamic evaluations of the SiO₂-TiO₂ phase diagram [25] and studies on the solubility of SiO_2 in rutile TiO_2 with varying pressures [26] 412 propose that there is no solubility between the respective oxides at atmospheric pressure and ambient 413 414 temperatures to about 1550 °C. It has been reported that additions of Si below 1 wt% Si in Ti-Si alloys 415 lead to a significant enhancement of the oxidation resistance due to a change in morphology of the top 416 TiO_2 layer improving the oxide scale adherence and preventing stratification [27]. These authors 417 suggested that Si in TiO₂ has an influence on the O vacancies which might lead to deceleration of the 418 diffusion rate of O in TiO₂ [27]. Conclusively, it is assumed that the presence of Si/SiO₂ in TiO₂ might 419 reduce the mobility of O and thereby improving its oxidation behaviour. The volume fractions and network structure of the respective oxides in the duplex scale were analysed after 100 h at 1200 °C in 420 421 order to determine the matrix forming oxide. The performed cluster analysis confirmed a mixed SiO₂-422 TiO₂ matrix character among all tested alloys, including the eutectic and eutectoid reference alloys. Especially, penetrating TiO₂ pathways were observed in all alloys. This reveals that an adequate 423 424 oxidation resistance is achieved even without a continuous SiO_2 matrix. As the oxidation behaviour is 425 characterised by the superposition of mass gain due to solid oxide growth and mass loss caused by 426 evaporation of MoO₃, the individual contributions were analysed at 1200 °C after 100 h highlighting the 427 dominant oxidation mechanism. It was found that evaporation of MoO₃ gains significance with 428 decreasing nominal Ti content. In the eutectic alloy, solid oxide growth predominates the oxidation 429 behaviour leading to the assumption that the forming oxide scale is passivating. These observations 430 might be transferred to lower temperatures explaining the outstanding oxidation behaviour of the 431 eutectic alloy at 800 °C. Moreover, the adequate oxidation resistance of the intermediate eutectic-432 eutectoid alloy A in the temperature regime of 800 to 1200 °C could be successfully combined with 433 satisfactory compressive creep resistance. At 1200 °C, alloy A possesses lower minimum creep rates 434 than the eutectic reference alloy while exhibiting the same creep mechanism. However, the apparent 435 difference in creep resistance was mainly caused by the different solidus temperatures of the alloys and, thus, different applied homologous temperatures. 436

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Appendix

443 As already described, the observed specific mass changes are resulting from two contributions:

$$\frac{m^{exp}}{A} = \frac{m_{O}^{scale}}{A} + \frac{m_{M_{O}}^{vapour}}{A}$$
(App. 1)
with $\frac{m_{O}^{scale}}{A} \ge 0$ and $\frac{m_{M_{O}}^{vapour}}{A} \le 0$

For the sake of clarity, *A* is omitted in the following because it is not changing significantly during oxidation. In the detail, the contributions to mass gain by scale growth can be itemized as follows:

448
$$m_0^{scale} = m_0^{duplex} + m_0^{top} + m_0^{internal}$$

449
$$= m_{O in TiO_2}^{duplex} + m_{O in SiO_2}^{duplex} + m_{O in TiO_2}^{top} + m_{O}^{internal}$$
(App. 2)

450 The contribution by internal oxidation is neglected for now: $m_0^{internal} = 0$. By using $m_{0 in TiO_2} =$ 451 $2 n_{TiO_2} M_0$ and $m_{0 in SiO_2} = 2 n_{SiO_2} M_0$, (App. 3) is obtained:

452
$$m_0^{scale} = 2 n_{TiO_2}^{duplex} M_0 + 2 n_{SiO_2}^{duplex} M_0 + 2 n_{TiO_2}^{top} M_0$$
(App. 3)

453 When applying $n = m/_M$ and $m = \rho V$, this transforms into:

454
$$m_0^{scale} = 2 M_0 \left(\frac{\rho_{TiO_2} V_{TiO_2}^{duplex}}{M_{TiO_2}} + \frac{\rho_{SiO_2} V_{SiO_2}^{duplex}}{M_{SiO_2}} + \frac{\rho_{TiO_2} V^{top}}{M_{TiO_2}} \right)$$
(App. 4)

The top layer is homogenous and its volume V^{top} is directly calculated from its thickness on the cuboid shape sample. The duplex layer is inhomogeneous and the respective volume fractions of the oxide phases as shown in Fig. 8 are utilized to calculate the respective volumes $V_{TiO_2}^{duplex} = v_{TiO_2}^{duplex} V^{duplex}$ and $V_{SiO_2}^{duplex} = v_{SiO_2}^{duplex} V^{duplex}$. The calculations shown in this article consider that the duplex layer is growing inward [6].

460
$$m_{O}^{scale} = 2 M_{O} \left[V^{duplex} \left(\frac{\rho_{TiO_{2}} v_{TiO_{2}}^{duplex}}{M_{TiO_{2}}} + \frac{\rho_{SiO_{2}} v_{SiO_{2}}^{duplex}}{M_{SiO_{2}}} \right) + V^{top} \frac{\rho_{TiO_{2}}}{M_{TiO_{2}}} \right]$$
(App. 5)

461 Hence,

462
$$m_{Mo}^{vapour} = m^{exp} - m_0^{scale}$$
(App. 6)

463 By applying n = m/M, the amounts of metallic species consumed in the oxidation processes can be 464 calculated:

465
$$n_{Mo}^{vapour} = \frac{m_{Mo}^{vapour}}{M_{Mo}}$$
(App. 7)

466
$$n_{Si}^{scale} = n_{Si}^{duplex} = n_{SiO_2}^{duplex} = \frac{m_{SiO_2}^{duplex}}{M_{SiO_2}}$$

467
$$= \frac{\rho_{SiO_2} v_{SiO_2}^{duplex}}{M_{SiO_2}} = \frac{\rho_{SiO_2}}{M_{SiO_2}} v_{SiO_2}^{duplex} V^{duplex}$$
(App. 8)

468
$$n_{Ti}^{scale} = n_{Ti}^{duplex} + n_{Ti}^{top} = n_{TiO_2}^{duplex} + n_{TiO_2}^{top}$$

469
$$= \frac{m_{TiO_2}^{duplex} + m_{TiO_2}^{top}}{M_{TiO_2}} = \frac{\rho_{TiO_2}}{M_{TiO_2}} \left(v_{TiO_2}^{duplex} V^{duplex} + V^{top} \right)$$
(App. 9)

470 Finally, the observed ratio of amounts of Si and Ti in the oxide scales to evaporating Mo is analysed: 471 $\frac{n_{\Sigma(si,Ti)}^{scale}}{n_{Mo}^{vapour}}$. The at first neglected internal oxidation further increases the obtained ratios. 472 Increasing ratios indicate faster growth rates of the solid scales than evaporation rates which is in 473 keeping with the observed oxidation stability at 1200 °C.

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Supplementary:



Suppl. 1 XRD diffraction patterns revealing evidence for the present phases in the as-cast state of alloy A and the heat-treated state of alloy B.



Suppl. 2 Specific weight change as a function of time during cyclic oxidation for the investigated alloys A and B at 1100 °C.



Suppl. 3 Specific weight change as a function of time during cyclic oxidation for the eutectic (a) and eutectoid (b) alloy.



Suppl. 4 Specific isothermal weight change of alloys A and B as a function of exposure time at 1100 °C (a) and 1200 °C (b).





Suppl. 5 BSE micrograph of the eutectic reference alloy cyclically oxidised at 800 °C after 1h (a) and 100 h (b). Overall images of alloy B (c) and of the eutectoid reference alloy (d) after cyclic oxidation at 800 °C after 100 h. BSE micrographs of oxidised samples at 1200 °C after 100 h of the eutectic (e) and eutectoid (f) alloy.



Suppl. 6 Respective Arrhenius plot for activation energy determination in alloy A.